

ABSTRACT OF THE DISCLOSURE

A substrate treating apparatus has an antireflection film forming block, a resist film forming block and a developing block arranged in juxtaposition, each of these blocks including treating modules and a single main transport mechanism. The main transport mechanism transports substrates within each block, and transfers the substrates between the blocks through inlet substrate rests and outlet substrate rests provided as separate components. This construction realizes improved throughput of the substrate treating apparatus.